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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/735,847	12/16/2003	Pertrus Rutgerus Bartray	081468-0307226	3169	
909	7590 07/14/2005		EXAM	EXAMINER	
PILLSBURY WINTHROP SHAW PITTMAN, LLP			NGUYEN, HUNG		
P.O. BOX 10500 MCLEAN, VA 22102			ART UNIT	PAPER NUMBER	
·			2851		
			DATE MAILED: 07/14/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)
Office Action Summan	10/735,847	BARTRAY ET AL.
Office Action Summary	Examiner	Art Unit
The BANK INC DATE of the	Hung Henry V. Nguyen	2851
The MAILING DATE of this communication ap Period for Reply	pears on the cover sheet with tr	ie correspondence address
A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a replif NO period for reply is specified above, the maximum statutory period. - Failure to reply within the set or extended period for reply will, by statut Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	.136(a). In no event, however, may a reply b ply within the statutory minimum of thirty (30) I will apply and will expire SIX (6) MONTHS i te, cause the application to become ABANDO	e timely filed days will be considered timely. rom the mailing date of this communication. DNED (35 U.S.C. § 133).
Status		
Responsive to communication(s) filed on <u>27 / 27 / 27 / 27 / 27 / 27 / 27 / 27 </u>	is action is non-final. ance except for formal matters,	
Disposition of Claims		
4) ☐ Claim(s) 1-23 is/are pending in the application 4a) Of the above claim(s) is/are withdra 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-23 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or Application Papers 9) ☐ The specification is objected to by the Examin	or election requirement.	
 10) ☐ The drawing(s) filed on 27 April 2005 is/are: a Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) ☐ The oath or declaration is objected to by the E 	e drawing(s) be held in abeyance. ction is required if the drawing(s) is	See 37 CFR 1.85(a). objected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
a) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document application from the International Bureat* See the attached detailed Office action for a list	nts have been received. Its have been received in Application of the contract	cation No eived in this National Stage
Attachment(s) Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date	4) Interview Summ Paper No(s)/Ma 5) Notice of Inform 6) Other:	

DETAILED ACTION

Prosecution Status

1. This office action is non-final rejection because the Examiner has changed the art and advanced new arguments.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. Claims 20-22 are rejected under 35 U.S.C. 102(e) as being anticipated by Harpaz (U.S. 2004/0204777 A1).

With respect to claims 20-22, Harpaz discloses a reference frame used in a lithographic apparatus (see section [004]) comprising all limitations of the instant claims such as: the reference frame (10) comprising a material (granite) having a coefficient of thermal expansion of greater than about 2.9x10⁻⁶/K and having a specific heat of greater than about 600 J/(kg.K). For example, please see table 1 of the specification on page 12, the coefficient of thermal expansion of Granite is about 5x 10⁻⁶/K and the specific heat is 820 (J/(kgK)).

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Claim Rejections - 35 USC § 103

4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claims 1-10, 12-23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shima (U.S.Pat. 6,822,727) in view of Harpaz (US 2004/0204777 A1).

As to claims 1-10, 12-23, Shima et al discloses an exposure apparatus for transferring a predetermined pattern formed on a mask onto a substrate and comprising substantially all of the limitations of the instant claims including: an illumination system (1-3) for providing a beam of radiation; a supporting structure (6) for supporting the mask (4); a substrate support (9) for supporting the substrate (8); a projection system (7) for projecting the patterned beam onto the substrate and a reference frame (FR) for providing a reference surface with respect to which a position of at least one of the substrate and the mask prior to exposure. Shima does not specifically disclose the reference frame made of a material having specific coefficient of thermal expansion, or a specific heat, and specific thermal conductivity as specified in the instant claims. Harpaz discloses a high precision position control apparatus for used in an exposure apparatus comprising reference frame (10) having a material (granite) having a coefficient of thermal expansion of greater than about 2.9x10⁻⁶/K and having a specific heat of greater than about 600 J/(kg.K). It would have been obvious to one having ordinary skill in the art at the time the invention was made to combine the teachings of Shima and Harpaz to obtain the invention as specified in the instant claims. It would have been obvious to a skilled artisan to employ suitable

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material having specific coefficient of thermal expansion, or a specific heat, and specific thermal conductivity as specified in the instant claims, as suggested by Harpaz to make the reference frame of Harpaz, for the purpose of preventing thermal expansion of the reference frame and improving the accuracy of the measuring system.

6. Claim 11 is rejected under 35 U.S.C. 103(a) being unpatentable over Shima (U.S.Pat. 6,822,727) in view of Harpaz (U.S 2004/0204777 A1) and further in view of Shiraishi (U.S.Pat. 6,020,950).

With respect to claim 11, Shima as modified by Harpaz, lacks to show a cooling device for controlling the temperature of the reference frame. Shiraishi teaches a cooling device for cooling a member of an exposure apparatus (see figure 5). It would have been obvious to a skilled artisan at the time the invention was made to combine the teachings of Shiraishi, Shima and Harpaz to obtain the invention as specified in claim 11 of the present application. It would have been obvious to a skilled artisan to employ the cooling device as taught by Shiraishi to cool off the reference frame of Shima as modified by Harpaz for the purpose of preventing the reference member from being deformed by thermal expansion and thus improving the quality of the exposure device.

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Response to Arguments

- 7. Applicant's amendment filed 4/27/2005 have been entered. Applicant's arguments with respect to prior art rejections have been carefully reviewed but have been traversed in view of new ground of rejections as set forth above.
- Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hung Henry V. Nguyen whose telephone number is 571-272-2124. The examiner can normally be reached on Monday-Friday (First Friday off).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Judy Nguyen can be reached on 571-272-2258. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Hung Henry V Nguyen Primary Examiner

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hvn 6/30/05